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On the Adsorption of DNA Origami Nanostructures in Nanohole Arrays

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ABSTRACT

DNA origami nanostructures are versatile substrates for the controlled arrangement of molecular capture sites with nanometer precision and thus have many promising applications in single-molecule bioanalysis. Here, we investigate the adsorption of DNA origami nanostructures in nanohole arrays which represent an important class of biosensors and may benefit from the incorporation of DNA origami-based molecular probes. Nanoholes with well-defined diameter that enable the adsorption of single DNA origami triangles are fabricated in Au films on Si
wafers by nanosphere lithography. The efficiency of directed DNA origami adsorption on the exposed SiO$_2$ areas at the bottoms of the nanoholes is evaluated in dependence of various parameters, i.e., Mg$^{2+}$ and DNA origami concentrations, buffer strength, adsorption time, and nanohole diameter. We observe that the buffer strength has a surprisingly strong effect on DNA origami adsorption in the nanoholes and that multiple DNA origami triangles with 120 nm edge length can adsorb in nanoholes as small as 120 nm in diameter. We attribute the latter observation to the low lateral mobility of once adsorbed DNA origami on the SiO$_2$ surface, in combination with parasitic adsorption to the Au film. While parasitic adsorption can be suppressed by modifying the Au film with a hydrophobic self-assembled monolayer, the limited surface mobility of the adsorbed DNA origami still leads to poor localization accuracy in the nanoholes and results in many DNA origami crossing the boundary to the Au film even under optimized conditions. We discuss possible ways to minimize this effect by varying the composition of the adsorption buffer, employing different fabrication conditions, or using other substrate materials for nanohole array fabrication.

INTRODUCTION

Since its introduction by Rothemund in 2006, the DNA origami technique with its remarkable versatility and ability to manufacture well-defined 2D and 3D nanoscale objects of almost arbitrary shape has become a wide spread method routinely employed in many labs around the world. DNA origami nanostructures are assembled by folding a long, single-stranded DNA scaffold into a pre-designed shape via hybridization with about 200 synthetic staple strands, each of which can be unambiguously identified in the assembled DNA origami construct via its unique nucleotide sequence. Therefore, DNA origami nanostructures can be site-selectively
decorated with functional entities such as reactive chemical groups, fluorophores, proteins, DNA topologies, metallic nanoparticles, and semiconductor quantum dots by incorporation of modified staple strands at selected positions. This great versatility has resulted in a broad range of applications that exploit the unprecedented structural control provided by the DNA origami technique. Functionalized DNA origami have for instance been utilized as substrates for single-molecule studies, as drug delivery vehicles, biosensors, and SERS substrates, as masks for molecular lithography, and as templates for the fabrication of electronic, plasmonic, and photonic nanostructures.

Many of the technological applications of DNA origami nanostructures critically rely on their precise placement on a substrate surface. Consequently, a large number of previous studies have evaluated various methods for the controlled immobilization and/or alignment of DNA origami nanostructures on different application-relevant materials. Most of the approaches reported in literature have employed top-down photo- or electron beam lithography to fabricate prepatterned substrate surfaces to direct DNA origami adsorption to chemically different micro- or nanoscale patches. Other studies have utilized receding menisci for the manipulation of already adsorbed DNA origami, or self-organized nanopatterns for the selective adsorption of DNA origami nanostructures.

In this work, we investigate directed DNA origami adsorption in nanohole arrays patterned into thin Au films on Si wafers by nanosphere lithography (NSL). NSL is a technique based on self-organization that enables the large-area patterning of surfaces with nanoscale features. To this end, (mono-) layers of nanospheres are assembled on solid surfaces by convective self-assembly of colloidal nanospheres from suspensions. Evaporation fluxes of the liquid medium of the suspension lead to an increased nanosphere concentration at a forming triple phase boundary.
between the liquid suspension, the solid substrate, and the surrounding gas phase. Along this triple phase boundary, capillary forces act on the nanospheres and draw them together, resulting in hexagonally close-packed nanosphere arrangements. In NSL, such nanosphere layers are used as a shadow mask in a subsequent deposition step\textsuperscript{35} during which material is deposited onto the nanospheres as well as onto the substrate through the mask openings in the nanosphere layer.

NSL enables the fabrication of various and often surprisingly complex patterns over large surface areas,\textsuperscript{38,39} which are for instance frequently used in protein patterning.\textsuperscript{39–41} On the other hand, NSL-fabricated nanohole arrays in Au films exhibit unique plasmonic properties\textsuperscript{42,43} and are thus used extensively in biosensing and on-chip bioanalysis.\textsuperscript{44,45} Immobilizing DNA origami nanostructures inside individual nanoholes may enable the introduction of single molecular capture sites and thereby provide additional benefits with regard to target specificity and sensitivity.\textsuperscript{46} While the specific adsorption of single biotin-carrying DNA origami nanostructures inside similar nanoholes has already been demonstrated using neutravidin-modified substrate surfaces,\textsuperscript{46} we here study non-specific DNA origami adsorption to the exposed SiO\textsubscript{2} surface at the bottom of the nanoholes in a Au film. In particular, we investigate the effect of buffer conditions on directed DNA origami adsorption in the nanohole arrays. We find that the strength of the adsorption buffer has a surprisingly strong influence and that the low surface mobility of once-adsorbed DNA origami is negatively affecting adsorption selectivity and positioning accuracy even under optimized conditions.

**MATERIALS AND METHODS**

**Nanosphere lithography.**

Epi-polished Si(100) wafers with native surface oxide were cleaned in a plasma of 2 sccm O\textsubscript{2} and 8 sccm Ar at a pressure of 75 mTorr and 50 W RF power for 5 minutes (Plasma Technology
Plasma Lab u80p). 7 µl droplets of an aqueous suspension of polystyrene (PS) nanospheres with a diameter of 202 nm (< 3 % coefficient of variance (CV), 5 % w/v solid content, Microparticles GmbH) were deposited onto the cleaned Si surfaces at a substrate temperature of 30°C. The droplet was driven across the Si surface with a hydrophobic blade at a constant velocity of 100 µm/s, resulting in the formation of a hexagonally close-packed nanosphere monolayer due to controlled solvent evaporation and capillary forces acting between the PS nanospheres.

The assembled PS nanospheres were exposed to an O₂/Ar plasma with the same parameters as reported above in order to remove part of the PS and shrink the nanospheres in diameter while maintaining their position on the substrate. The final diameter can be controlled by the duration of the plasma treatment: here, a treatment for 45 sec was used to reduce the nanosphere diameter from 202 nm to 160 nm; after 90 sec the diameter reaches 120 nm.

10 nm Au were deposited onto the samples by electron beam evaporation. To ensure conformal growth of the Au film, 2 nm Ti were deposited prior to Au as adhesion promoter without breaking the vacuum (base pressure 5 x 10⁻⁶ mbar) between deposition steps. After deposition, the nanospheres were removed by chemical dissolution in tetrahydrofuran (Carl Roth) in an ultrasonic bath. Carbon residues from the PS nanospheres which remained on the Si surface after ultrasonication were removed by dipping the samples into a 10 % aq. HF (Carl Roth) solution for 5 seconds. This harsh cleaning procedure was necessary since alternative treatments were not able to remove all the carbon residues (see figure S1).

**Scanning electron microscopy (SEM).**

SEM images were taken with a Raith Pioneer at an acceleration voltage of 5 kV using the in-lens detector. Image analysis was performed with a home-made software. The nanohole diameters
were evaluated by a grey-scale thresholding technique, the density and coordination by a Delaunay triangulation-based algorithm.

**DNA origami assembly.**

DNA origami triangles were synthesized as described previously, using the M13mp18 scaffold (Tilibit) and 208 staple strands (Metabion). Assembly was performed in 1x TAE (Carl Roth) with 10 mM MgCl₂ (Sigma-Aldrich) by stepwise thermal annealing in a thermocycler Primus 25 advanced (PEQLAB). Excess staples were removed after assembly by spin filtering using 100 kDa MWCO filters (Amicon Ultra, Millipore). After filtering, the DNA origami concentration was measured by UV/Vis absorption with an Implen Nanophotometer P330.

**DNA origami adsorption.**

The nanohole array substrates were first cleaned with ethanol and water. A mild oxygen plasma cleaning (Zepto, Diener electronic) was carried out for 1 min with 50 % power before DNA origami adsorption. For DNA origami adsorption, 1x TAE and 2.5x TAE stock solutions were prepared with 10 mM MgCl₂. For the higher MgCl₂ concentration of 50 mM, working solutions were freshly prepared by adding the required volume from a 1 M MgCl₂ stock solution. All buffer solutions had a pH of 8.5. The DNA origami sample was then diluted in the respective buffer solutions to the desired concentrations. The nanohole array substrate was placed on a stage inside a humidity chamber to avoid evaporation and 100 µl of the resulting sample solution were slowly dropped on the surface. After incubation, the sample was carefully washed with 4 ml of HPLC-grade water (VWR) and dried in a stream of ultrapure air.

**Self-assembled monolayer (SAM) fabrication.**
Plasma-cleaned nanohole array samples were immersed in 1 mM 1-octadecanethiol (ODT, Sigma-Aldrich) in ethanol for 24 h to form hydrophobic SAMs on the surfaces of the Au films. Immediately before the adsorption experiments, the SAM-coated nanohole arrays were rinsed with ethanol and dried in a stream of ultrapure air. The ODT SAMs formed under these conditions exhibit high packing densities and render the Au surface fully hydrophobic.49

Atomic force microscopy (AFM).

The samples were imaged in intermittent contact mode in air using an Agilent 5100 AFM and HQ: NSC18/Al BS cantilevers (MikroMasch). Yields are presented as averages over three AFM images taken at different positions on the sample surface with standard deviations as error bars. A minimum 600 individual nanoholes were analyzed for each condition.

RESULTS AND DISCUSSION

The experimental strategy is schematically summarized in figure 1. Ordered nanohole arrays are fabricated by NSL. To this end, hexagonally close-packed monolayers of PS nanospheres are assembled on a Si wafer by convective self-assembly using the doctor blade technique.50 The assembled PS nanospheres are then shrunk by exposure to an O₂/Ar plasma to create an array of well-separated yet hexagonally ordered nanospheres. The shrunk nanospheres then act as a shadow mask for physical vapor deposition. A 10 nm thin Au film is deposited onto the sample, i.e., the shrunk nanospheres and bare SiO₂ in the gaps between the nanospheres. Lift-off of the nanospheres by dissolution uncovers the final surface pattern, i.e., a thin Au film exhibiting hexagonally arranged nanoholes which expose the untreated SiO₂ surface at their bottoms. These confined SiO₂ surfaces at the bottoms of the nanoholes are then used to direct DNA origami adsorption.
**Figure 1.** Experimental strategy: A hexagonally ordered pattern of nanoholes in a thin Au film on a Si wafer is fabricated by NSL and used to direct the adsorption of DNA origami nanostructures.

The fabricated nanohole patterns are characterized in figure 2. Analysis of the SEM images reveals a diameter of the nanoholes of $160 \pm 16$ nm and a nanohole density of $2.6 \times 10^9$ cm$^2$ over substrate areas of several cm$^2$. In addition, 95% of the nanoholes show perfect sixfold coordination with < 2% of defects occurring due to dislocation lines or grain boundaries and approximately 3% point defects. The AFM height profile shown in figure 2e reveals a thickness of the Ti/Au film between 10 and 12 nm, in good agreement with the nominal thicknesses deposited of 2 nm Ti and 10 nm Au. The optical properties of these nanohole arrays are characterized in figure S2. The nanohole diameter of 160 nm allows for adsorbing single triangular DNA origami nanostructures with an edge length of about 120 nm. Due to the lateral confinement of the exposed SiO$_2$ area by the surrounding Au film, adsorption of more than one DNA origami triangle per nanohole should be restricted. However, since adsorption of the negatively charged DNA origami nanostructures to the negatively charged SiO$_2$ patches requires divalent cations such as Mg$^{2+}$ in order to form salt bridges between DNA and surface, adsorption
efficiency and especially selectivity can be expected to critically depend on buffer conditions.\textsuperscript{32} Therefore, we have first evaluated the role of Mg\textsuperscript{2+} concentration and buffer strength on DNA origami adsorption in the nanoholes.

\begin{figure}
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\caption{a-d) SEM images of the assembled nanosphere monolayers before (a) and after (b) plasma shrinking, and the resulting nanohole array (c,d). e) AFM image of the nanohole array and corresponding height profile taken along the black line indicated in the AFM image.}
\end{figure}

Figure 3a shows AFM images of nanohole patterns after adsorption of 1 nM DNA origami triangles in different buffers for 1 h. Obviously, both buffer strength and Mg\textsuperscript{2+} concentration have significant effects on DNA origami adsorption. Increasing the MgCl\textsubscript{2} concentration from 10 to 50 mM in 1x TAE results in significantly higher DNA origami coverage of the exposed SiO\textsubscript{2} areas. In particular, as the statistical analysis in figure 3a reveals, the fraction of empty nanoholes decreases from more than 70 % at 10 mM MgCl\textsubscript{2} to only about 10 % in 50 mM MgCl\textsubscript{2}. Surprisingly, however, this results in only about 40 % of the nanoholes being occupied by a single DNA origami, whereas half of the nanoholes exhibit two or even three DNA origami
nanostructures. Considering the nominal edge length of the triangles and the average diameter of the nanoholes of 120 nm and 160 nm, respectively, this double and triple occupation can result from two or three DNA origami triangles stacking on top of each other or from only partial adsorption of one or more DNA origami triangles inside the nanoholes with a part of the triangle crossing the boundary to the Au film. Upon closer inspection, examples of both mechanisms can be observed on one sample surface (see figure 3b). However, a statistical analysis reveals that partial adsorption of DNA origami nanostructures accounts for about 63 % of multiply-occupied nanoholes, while only 37 % show vertical stacking. Note that partial adsorption is also frequently observed for singly-occupied nanoholes (see figure 3b, panel 3).
Figure 3. a) AFM images (1 x 1 µm², height scales 3 nm) and corresponding statistical analyses of DNA origami triangles adsorbed in the nanohole arrays for two buffer strengths and two MgCl₂ concentrations. The DNA origami concentration was 1 nM and the incubation time 1 h. b) Zoomed AFM images of 1) multiple DNA origami nanostructures adsorbed in single nanoholes via vertical stacking, 2) multiple DNA origami nanostructures adsorbed in single nanoholes via partial adsorption, and 3) single DNA origami nanostructures adsorbed in single nanoholes via partial adsorption. The DNA origami concentration was 1 nM in 1x TAE with 50 mM MgCl₂ and the incubation time 1 h.

Increasing the buffer strength to 2.5x TAE at a constant MgCl₂ concentration of 10 mM results also in a decrease in the fraction of empty nanoholes and a moderate increase in the fraction of
nanoholes occupied by a single DNA origami triangle to about 30 % (see figure 3). However, the fraction of higher occupancies remains below 10 %. Increasing the MgCl$_2$ concentration to 50 mM again leads to a further decrease in the fraction of empty nanoholes which, however, is not as strong as in the case of 1x TAE. This is also reflected in the fraction of singly-occupied nanoholes which remains rather constant. These results demonstrate the non-trivial interplay of buffer strength and Mg$^{2+}$ concentration in DNA origami adsorption to SiO$_2$ surfaces. Due to the large fraction of nanoholes occupied by more than a single DNA origami triangle at high MgCl$_2$ concentrations, we have used the lower concentration of 10 mM in all the following experiments. Apart from the buffer conditions, also the DNA origami concentration will affect surface coverage and thereby the occupation of the nanoholes. The effect of DNA origami concentration is therefore evaluated in figure 4, again for two different buffer strengths. Surprisingly, increasing the DNA origami concentration in 1x TAE from 1 nM to 5 nM does not result in any noticeable increase in the DNA origami density. In particular, the fraction of empty and singly-occupied nanoholes remains at about 70 % and about 25 %, respectively, independent of DNA origami concentration.
Figure 4. AFM images (1 x 1 µm², height scales 3 nm) and corresponding statistical analyses of DNA origami triangles adsorbed in the nanohole arrays for two buffer strengths and three DNA origami concentrations. The MgCl₂ concentration was 10 mM and the incubation time 1 h.

At the higher buffer strength of 2.5x, the situation is notably different. As can be seen in figure 4, increasing the DNA origami concentration from 1 nM to 2.5 nM results in a drastic decrease in the fraction of empty nanoholes from about 60 % to roughly 10 %. At the same time, the fraction of nanoholes occupied by a single DNA origami triangle increases from about 30 % to about 50
%. At this DNA origami concentration, the second most dominant population is represented by
nanoholes occupied by two DNA origami triangles at about 35 %. Further increase of the DNA
origami concentration to 5 nM, however, does not result in any significant changes in these
numbers.

Finally, we set out to investigate the influence of adsorption time on directed DNA origami
adsorption in the nanohole arrays. For these experiments, we used a DNA origami concentration
of 1 nM since this concentration resulted in the lowest fractions of multiply-occupied nanoholes
(see figure 4). Increasing the incubation time in 1x TAE was found to result in a continuous
decrease in the fraction of empty nanoholes from about 75 % after 1 h incubation to about 40 %
after 12 h (see figure 5). At the same time, the fraction of singly-occupied nanoholes increases
from about 20 % to about 50 %. Remarkably, the fraction of multiply-occupied nanoholes
increases only marginally with incubation time and reaches roughly 10 % after 12 h incubation.

A higher buffer strength of 2.5x again results in drastically different behavior. Here, the fraction
of singly-occupied nanoholes is steadily decreasing with incubation time, from about 30 % after
1 h to almost 0 % already after 3 h of incubation. This decrease is due to a dramatic increase in
the number of adsorbed DNA origami triangles per nanohole. After 3 h of incubation, the
majority of nanoholes, i.e. around 50 %, is occupied already by three DNA origami, while more
than 40 % of the nanoholes exhibit two DNA origami triangles. After 12 h of incubation,
virtually all the nanoholes are occupied by three or more DNA origami nanostructures.
Figure 5. AFM images (1 x 1 µm², height scales 3 nm) and corresponding statistical analyses of DNA origami triangles adsorbed in the nanohole arrays for two buffer strengths and three incubation times. The MgCl₂ and DNA origami concentration was 10 mM and 1 nM, respectively.

Above results demonstrate the tremendous importance of buffer strength in DNA origami adsorption in general and directed adsorption in particular. Based on these data, it appears
possible to obtain a yield of nanoholes occupied by only a single DNA origami triangle of more than 50 %, in particular by using low buffer strengths, low Mg$^{2+}$ concentrations, low DNA origami concentrations, and long incubation times of 12 h and more. However, even under optimized conditions, many of the single DNA origami nanostructures are not fully located inside the nanoholes but rather cross the boundary to the Au film (see figures 3 and 5). This partial DNA origami adsorption may result from two different effects. A low lateral mobility of the adsorbed DNA origami nanostructures at the SiO$_2$ surface may prevent them from maximizing their contact area with the oxide surface and thereby centering themselves in the nanoholes. On the other hand, DNA origami may also adsorb to the surface of the Au film which – in the case of comparable affinities for Au and SiO$_2$ – would result in random adsorption instead of directed immobilization.

If low surface mobility of the DNA origami on the SiO$_2$ surface was responsible for the observed partial adsorption in the nanoholes, reducing the diameter of the nanoholes to approach the size of the DNA origami should lead to higher yields of singly-occupied nanoholes due to stronger lateral confinement. Therefore, we have prolonged the plasma exposure of the assembled nanospheres to reduce their diameter to 120 nm so that it matches the size of the DNA origami triangles (see figure S3). Figure 6 shows AFM images and the corresponding statistical analyses of DNA origami triangles adsorbed in the nanohole patterns with 120 nm and 160 nm diameter. The adsorption conditions were chosen to result in a yield of about 50 % singly-occupied and 50 % multiply-occupied nanoholes with 160 nm diameter (see figure 4). As can be seen in figure 6, very similar distributions are obtained for both nanohole sizes. The only visible difference between the statistical distributions in figure 6 is the apparent lack of 120 nm nanoholes occupied by three DNA origami triangles. This may be a result of the small nanohole size that
even in the case of partial adsorption cannot accommodate more than two DNA origami triangles. On the other hand, the small nanohole diameter makes identification of individual DNA origami nanostructures inside the nanoholes quite difficult and may thus introduce a bias in the statistical evaluation shown in figure 6. Nevertheless, these results demonstrate that partial adsorption of DNA origami nanostructures cannot be significantly reduced by using smaller nanohole diameters, thus hinting at the relevance of parasitic adsorption to the surface of the Au film.

![AFM images and statistical analyses](image)

**Figure 6.** AFM images (1 x 1 µm², height scales 3 nm) and corresponding statistical analyses of DNA origami triangles adsorbed in a 160 nm nanohole array and a 120 nm nanohole array. Adsorption conditions were 2.5 nM DNA origami in 2.5x TAE with 10 mM MgCl₂ for 1 h.

Due to the comparatively high roughness of the deposited Au film, we are unable to identify DNA origami triangles crossing from the bottoms of the nanoholes to the surface of the Au film in the AFM images (see figure S4). On smoother template-stripped Au surfaces, however, a significant amount of adsorbed DNA origami can be detected even at low DNA origami and MgCl₂ concentrations (see figure S5). This indeed suggests that parasitic DNA origami adsorption to the surface of the Au film interferes with directing adsorption to the bottoms of the nanoholes. Therefore, we have modified the surfaces of the Au films of 160 nm nanohole arrays with a hydrophobic, CH₃-terminated thiol SAM in order to minimize non-specific DNA origami...
adsorption. The effect of this SAM has been evaluated for selected conditions which in the
previous experiments resulted in high DNA origami coverage (figure 7). Indeed, for all
conditions evaluated, application of the hydrophobic SAM resulted in significantly reduced DNA
origami adsorption. This clearly demonstrates the strong influence of non-specific adsorption to
the Au film. However, at low incubation times, the reduced overall adsorption results in a major
fraction of the nanoholes remaining empty, while long incubation times lead to distributions with
significant, albeit drastically reduced fractions of multiply occupied nanoholes. The latter seems
to be a direct result of the fact that many DNA origami are still not fully located inside the
nanoholes but cross the boundary to the Au film. Since non-specific DNA origami adsorption to
the gold film is blocked by the hydrophobic SAM, these observations can only be explained by
the low lateral mobility of the adsorbed DNA origami nanostructures at the SiO$_2$ surface. These
results thus proof that both effects, low surface mobility on the SiO$_2$ surface and parasitic
adsorption to the Au surface, negatively affect adsorption specificity.

**CONCLUSION**

The here presented study has identified several key parameters for optimizing adsorption
specificity of DNA origami nanostructures in nanohole arrays on SiO$_2$ surfaces. In particular,
comparatively high yields of nanoholes occupied by single DNA origami may be obtained for
low DNA origami and MgCl$_2$ concentrations of about 1 nM and 10 mM, respectively, low buffer
strength, and long incubation times exceeding 12 h. Furthermore, the strength of the adsorption
buffer was found to have a surprisingly strong influence on directed DNA origami adsorption
and may drastically alter the dependencies on the other parameters. However, even under
optimized conditions, many of the adsorbed DNA origami are not located completely inside the
nanoholes but rather cross the boundary to the surrounding Au film. This partial DNA origami
adsorption can be attributed to parasitic adsorption of DNA origami to the surface of the Au film and the low surface mobility of adsorbed DNA origami on the SiO$_2$ surface which prevents them from maximizing their contact area with the oxide surface.

Figure 7. AFM images (1 x 1 µm$^2$, height scales 3 nm) and corresponding statistical analyses of DNA origami triangles adsorbed under different conditions in 160 nm nanohole arrays with (+ SAM) and without (- SAM) application of a hydrophobic thiol SAM. DNA origami concentrations, buffer strengths, and incubation times are given in the figure.

While we have shown that parasitic adsorption to the Au film can be minimized by application of a hydrophobic thiol SAM, the problem of reduced lateral mobility could not be solved so far and may be affected by a number of parameters. In the present work, we have focused on TAE buffer
supplemented with MgCl₂ since this is probably the most widely used buffer in DNA origami assembly. However, alternative buffer compositions may result in higher lateral mobility of once adsorbed DNA origami nanostructures and thus improved localization accuracy. It was for instance shown that addition of high concentrations of Na⁺ ions may increase the lateral mobility of DNA origami nanostructures on mica due to a partial replacement of Mg²⁺ ions from the mica surface which results in a reduced positive surface charge and thus weaker electrostatic interactions with the negatively charged DNA origami.¹⁶,⁵¹ Similarly, DNA binding to mica surfaces may also be adjusted by using different divalent cations.⁵² The case of DNA origami adsorption to SiO₂ surfaces, however, is more complicated. In particular, charge inversion of the SiO₂ surface due to adsorption of divalent cations such as Mg²⁺ and Ca²⁺ occurs at much higher cation concentrations (300 to 400 mM) than used in the present work.⁵³ Since charge inversion of DNA in solution requires even higher Mg²⁺ concentrations,⁵⁴ DNA origami adsorption under the current experimental conditions is likely facilitated by specific Mg²⁺ salt bridges forming between the terminating silanol groups of the SiO₂ surface and the phosphates in the DNA backbone.²⁹ In this case, using other divalent cations may result in very different and so far unexplored DNA origami binding behaviors. The charge of the SiO₂ surface, the adsorption of cations, and the formation of Mg²⁺ salt bridges furthermore depend on the protonation state of the terminating silanol groups and thus on pH.⁵⁵ Adjustment of the pH of the adsorption buffer may therefore represent another viable route toward optimizing localization accuracy. All these issues deserve in-depth investigation in future studies.

Surface mobility of the DNA origami nanostructures may also be affected by the fabrication process of the nanoholes and especially the different plasma treatment steps, as it is well known that the surface energy of SiO₂ crucially depends on the nature and history of the specimens.⁵⁶
Furthermore, since most nanohole array sensors require optical access to both interfaces of the metal film, other transparent substrates such as the multitude of optical glasses but also sapphire or indium tin oxide are worth investigating with regard to DNA origami adsorption and may provide higher localization accuracy.

As an alternative strategy, the DNA origami design may be tailored with regard to the nanohole dimension and geometry. For the circular nanoholes used in the present study, a disk-shaped DNA origami with the same diameter as the nanoholes may occupy the whole surface area available at the bottom and thus be able to block or at least reduce partial adsorption of other DNA origami disks in the same nanohole. However, due to the limited scalability of DNA origami size, this approach will be restricted to a rather narrow range of nanohole diameters. Since single-layer DNA origami nanostructures other than the triangles used here are typically rather floppy and show a certain tendency to rolling up, stiffer multilayer DNA origami are most likely more efficient in avoiding partial adsorption. This, however, will restrict the accessible size range even further.

Finally, the nanohole arrays employed in above studies feature a rather thin Au film of 10 to 12 nm thickness (see figure 2e) in order to facilitate imaging of the bottoms of the nanoholes by AFM. For most plasmonics-based sensing applications, however, films with thicknesses of the order of 100 nm are required. For such nanohole arrays, diffusion of the comparatively large DNA origami nanostructures through the narrow nanochannels will affect adsorption kinetics and become more and more dominant the closer the nanohole diameter approaches the size of the DNA origami. On the other hand, higher sidewalls may also more efficiently confine the DNA origami to the exposed SiO\textsubscript{2} surface and thus further reduce the occurrence of partial DNA origami adsorption, especially for mechanically rigid DNA origami designs.
ASSOCIATED CONTENT

Supporting Information: Comparison of cleaning procedures; optical characterization of the nanohole arrays by ellipsometry; SEM images of a monolayer of nanospheres shrunk to 120 nm diameter and the resulting nanohole array; additional AFM images of the 160 nm nanohole array after adsorption of 1 nM DNA origami in 1x TAE with 50 mM MgCl$_2$; AFM image of a template-striped Au surface after DNA origami incubation.

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Author Contributions

The manuscript was written through contributions of all authors. All authors have given approval to the final version of the manuscript. # These authors contributed equally.

Notes

The authors declare no competing financial interest.

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